

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: HAGIWARA, et al.

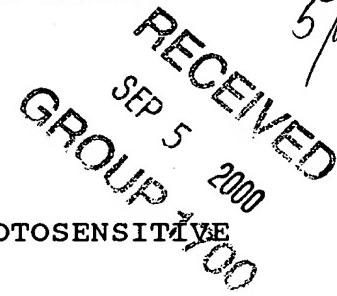
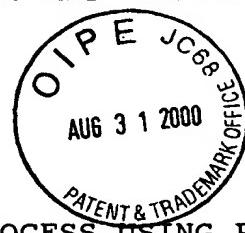
Serial No.: 09/482,859

Filed: January 14, 2000

For: PATTERN FORMING PROCESS USING PHOTORESISTIVE  
RESIN COMPOUND

Group: 1752

Examiner: J. Chu

RESPONSEAssistant Commissioner for Patents  
Washington, D.C. 20231

August 31, 2000

Sir:

In response to the Office Action mailed June 1, 2000, setting a three-month shortened statutory period for response, Applicants respectfully elect the Group I claims (claims 1-9, drawn to a semiconductor device). This election is made without traverse.

In view of the foregoing, consideration of the Group I claims, on the merits, in due course, is respectfully requested.

To the extent necessary, Applicants petition for an extension of time under 37 CFR § 1.136. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to the Deposit

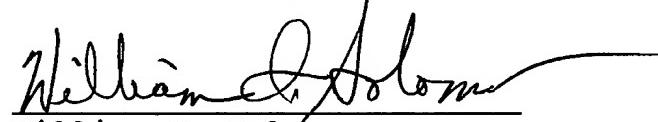
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Account No. 01-2135 (Case No. 511.33114VV4) and please credit  
any excess fees to such Deposit Account.

Respectfully submitted,

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WIS/slk